



Key components 设备单元



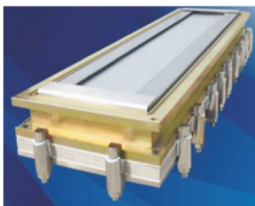
Rotary Cathode Sputtering
柱靶阴极



Planar Cathode Sputtering
平面阴极



Sputtering Deposition
溅射镀膜



Ion Source
离子源



High Vacuum Valve
高阀



Sputtering Power Supply
溅射电源

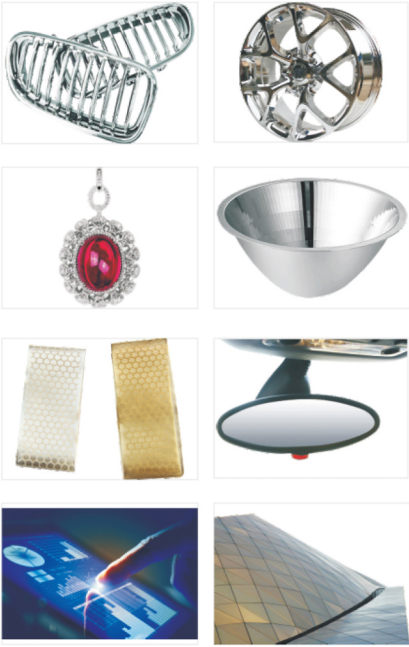
MAGNETRON SPUTTERING

COATER 磁控溅射镀膜设备

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Descriptipn 描述



RTSP系列真空磁控溅射镀膜机主要用于导电/不导电功能膜，装饰性镀膜。

1. **应用**：显示器，触摸屏上的ITO导电膜，幕墙玻璃；汽车轮毂，汽车后视镜，汽车大灯、尾灯，汽车内外塑料装饰件；餐具，厨房用具；首饰，运动产品，玩具；替代水电镀应用行业等。

2. **可溅射多种金属和金属化合物**：钛，铬，钨及其金属合金，铜，铝，不锈钢，镍等金属；钛铝合金，镍镉合金，氧化钨锡，DLC膜等。

磁控溅射光学膜：AR膜，硬质疏水膜等。

3. **溅射方式**：直流，中频，射频。

4. **特点**：低温镀膜，成膜快速、稳定。

RTSPseries coating equipment is used for the production of conductive,non-conductive functional coatings, aesthetic purpose.

1. **Applications:** ITO coatings on glass for touch screens, displays; architectural glass; automotive industry: car wheels & rims, car mirrors, head lamps, tail lights, plastic interior & exteriors; tableware & kitchenware, jewelry, sport and toys, water-electroplating replacement.

2. **Coating materials:**

Metals: Ti (Titanium), Cr(Chromium), Zr (Zirconium), Cu (Copper), Al (Aluminum), Ni (Nickel), SUS316 (Stainless steel) ...

Metal Alloys: Ti-Al alloy, Ni-Ca alloy (Nickel - Cadmium), ITO (Indium Tin Oxide), DLC (diamond like carbon) film.

3. **Sputtering methods:** DC/MF/RF .

4. **Coating properties:** low-temperature coating, fast deposition and reliable quality.

MSC Standard 标准镀膜设备

Model 型号	Size(mm) 尺寸	Number of Planetary Rods 行星体转轴数量	Sputtering Power(kVA) 溅射电源	Sputtering Cathodes (Qty.) 溅射阴极数量	Magnetron Sputtering Technology 磁控溅射技术	MFC 气体质量控制 流量计	Remark 备注
RTSP1250	Φ1250xH1250	6	2* 30 DC/MF	2	Balanced, Unbalanced 平衡,非平衡	2~4, depends on coating process, 2~4路，取决于 镀膜工艺	High quality decoration coating 高端装饰镀膜
RTSP1400	Φ1400xH1250	6, 8	2*36 DC/MF	2			
RTSP1600	Φ1600xH1250	6,8,12	2*48 DC/MF	2			
RTSP1616	Φ1600xH1600	6,8	2*36 DC	2	Planar Target 平面靶		2-door 双开门

MSC Customized 订制镀膜设备

Model 型号	Size(mm) 尺寸	Number of Planetary Rods 行星体转轴数量	Sputtering Power(kVA) 溅射电源	Sputtering Cathodes (Qty.) 溅射阴极数量	Magnetron Sputtering Technology 磁控溅射技术	MFC 气体质量控制 流量计	Remark 备注
RTSP900	Φ900xH900	1	1*24 DC	1	Planar Target 平面靶	2~4, depends on coating process 2~4路， 取决于 镀膜工艺	Automotive rim, interior & exterior trims 汽车轮毂 内外装饰
RTSP1315	Φ1300xH1500	1	1*48 DC	1	Planar Target 平面靶		
RTSP1618	Φ1600xH1800	2	2*72 DC	2	Planar Target 平面靶		
RTSP800	Φ800xH800	1	2*50 DC	4	Cylinder or Planar 柱靶或平面靶		ITO, AR